Attorney Docket No. 5649-873

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

n re: Koh et al.

Group Art Unit: 2811 Examiner: Thien F. Tran

Serial No.: 09/891,905

Filed: June 26, 2001

METHODS OF FORMING INTEGRATED CIRCUITS USING MASKS TO

PROVIDE ION IMPLANTATION SHIELDING TO PORTIONS OF A SUBSTRATE ADJACENT TO AN ISOLATION REGION THEREIN (As

amended)

February 7, 2002

BOX NON-FEE AMENDMENT Commissioner for Patents Washington, DC 20231

AMENDMENT

Sir:

For:

This amendment is responsive to the Restriction Requirement of January 29, 2002. The present amendment also includes a section entitled "VERSION WITH MARKINGS TO SHOW CHANGES MADE" attached hereto.

In the Specification:

Please replace the title with the following rewritten title:

--METHODS OF FORMING INTEGRATED CIRCUITS USING MASKS TO PROVIDE ION IMPLANTATION SHIELDING TO PORTIONS OF A SUBSTRATE ADJACENT TO AN ISOLATION REGION THEREIN--.

In the Claims:

Please cancel Claims 5-6, without prejudice to the filing of any divisional application based on the present application.

Amor A 3/15/02 VS

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